- **8**. The housing of claim **1**, wherein the hard layer is composed of diamond-like carbon, and wherein the abrasion-resistant coating is characterized as having a Vickers hardness ranging between about 1000 HV0.5 and about 1500 HV0.5.
- 9. The housing of claim 8, wherein the intermediate layer is characterized as having a Vickers hardness ranging between about 400 HV0.5 and about 600 HV0.5.
- 10. The housing of claim 1, wherein the metal portion is composed of an aluminum alloy having a zinc concentration of at least about 2 weight %.
 - 11. A part, comprising:
 - a metal substrate; and
 - an abrasion-resistant coating disposed on the metal substrate, the abrasion-resistant coating including:
 - an external layer composed of a diamond-like carbon material, and
 - an intermediate layer between the external layer and the metal substrate, the intermediate layer composed of a porous oxide.
- 12. The part of claim 11, wherein the external layer has a thickness ranging between about 0.5 micrometers and about 3 micrometers.
- 13. The part of claim 12, wherein the intermediate layer has a thickness ranging between about 8 micrometers and about 30 micrometers.
- **14**. The part of claim **11**, wherein the porous oxide has pores with a colorant infused therein.

- 15. A method of forming an abrasion-resistant coating on a housing for an electronic device, the housing having a metal portion defining a cavity suitable for carrying internal electronic components, the method comprising:
 - converting a portion of the metal portion to a porous oxide layer; and
 - depositing a hard layer on the porous oxide layer, wherein the hard layer is characterized as having a greater hardness than the porous oxide layer.
- **16**. The method of claim **15**, wherein depositing the hard layer comprises depositing a portion of the hard layer within pores of the porous oxide layer.
- 17. The method of claim 15, wherein the hard layer is composed of at least one of a carbide, a nitride, a diamond-like carbon, or a hard oxide.
- **18**. The method of claim **15**, further comprising lapping the porous oxide layer prior to depositing the hard layer.
- 19. The method of claim 15, further comprising superficially sealing the porous metal oxide layer by exposing the porous metal oxide layer to a hot aqueous solution for 60 seconds or less.
- **20**. The method of claim **15**, wherein the porous oxide layer is grown to a thickness ranging between about 8 micrometers and about 30 micrometers, and the hard layer is deposited to a thickness ranging between about 0.5 micrometers and about 3 micrometers.

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